CMOS Active Pixel Image Sensors: Past, Present, and Future

Dr. Eric R. Fossum January 2008





12/31/2007 D. Snyder – night handheld no flash

Early History of Image Sensors

- 1963 Morrison Honeywell
 - Light spot position "computational" sensor
- 1964 Horton, et al. IBM
 - The "scanistor"
- 1966 Schuster & Strull -Westinghouse
 - 50 x 50 element phototransistor array
- 1967 Weckler Fairchild
 - Charge integration on a floating pn junction
- 1967 Weimer, et al. RCA
 - 180x180 TFT element self-scanned sensor
 - Battery powered, wireless camera

- 1968 Dyck & Weckler Fairchild
 - "Passive pixel" photodiode array ("reticon")
 - 100 x 100 element array
- 1968 Noble Plessey
 - Passive pixel photodiode array
 - On-chip charge integrating amplifier
 - Buried photodiode structure
 - Source-follower buffer in pixel
 - Lots of problems Vt instability, FPN
- 1970 Boyle, Smith, Amelio, Tompsett AT&T Bell Labs
 - Charge-coupled semiconductor devices (CCDs)

CCD Operation

• Charge-coupled devices shift charge one step at a time to a common output amplifier



Charge-Coupled Devices

<u>CCDs were better</u>

- Smaller pixel sizes (3 electrodes/pixel)
- Lower readout noise
- No fixed pattern noise
- Low on-chip power dissipation
- Interesting device physics

<u>CCDs have limitations</u>

- Requires high charge transfer efficiency
 - Special fabrication process
 - Large voltage swings, different voltage levels
 - Radiation "soft" in space environment
 - Limits readout speed
- Difficult to integrate on-chip timing, control, drive and signal chain electronics
- Serial access to image data
- System power in 1-10 Watt range

Timeline



111 Mpix Charge-Coupled Device

5

P2

P3

P2

OS-

RD

RG-

VID

RTN

Eight 10 Mhz Outputs

Image Region 10560x5280

 \sim

P2

P

P1 P2

R. Bredthauer et al. 2007 IISW P3 P3 P2 P2 P3 P3 Image Region 10560x5280 P1 P2 P3 P1 P2 0 Eight 10 Mhz Outputs **Figure 1** Configuration RMS Noise (e-)

Figure 3 STA1600 Wafer



1320 (H) x 5280 (V) Imaging Array

Output Register

81 82 83

Figure 2 Single

Figure 4 Noise vs

Passive Pixel MOS Image Sensor

- Like DRAM
- Single switch for reset and readout
- Charge read out at array corner or amplified at bottom of column.
- Approach taken initially by Hitachi, VVL (ST), Omnivision and others
- Too much noise and FPN to compete with CCD
- Allows integration of other circuits on same chip



Active Pixel Image Sensors

Amplifier inside pixel

- Olympus Charge Modulated Device (CMD)
- TI Bulk Charge Modulated Device (BCMD)
- Canon Base-Stored Image Sensor (BASIS)
- Olympus SIT Image Sensor
- All "tricky" devices to make and require highly specialized fab process.
 - Hard to make, hard to manufacture
 - Difficult to evolve to smaller process features
 - No compelling reason for industry to switch

Active Pixel Image Sensors

- NHK Amplified MOS Image Sensor
 3T PD type
 - Almost got it right but readout chain sensitive to MOSFET "on resistance" and hence large FPN

Driving Forces

- CCD development in the 1980's driven by camcorder market
 - Solid-state much better than tubes for consumer
- CMOS image sensor development in the later 1990's, 2000's driven by camera phone market
 - Lower power, higher integration, small form factor, lower cost for same functions.

CMOS Active Pixel Image Sensor

- Invented at NASA/JPL 1992 (patents owned by Caltech)
- Used vanilla CMOS process available at many foundries
- Single-stage "CCD" in each pixel to allow complete charge transfer
- In-pixel source-follower amplifier for charge gain
- Allows low noise CDS operation
- In-column FPN reduction
- Permitted high performance camera-on-a-chip
- Basis of all modern CMOS image sensors

Advantages of CMOS Image Sensors

- CMOS Camera-on-a-chip technology is <u>better</u> than CCDs because:
 - Much lower power important for portable applications
 - System-on-a-chip integration allows smaller cameras
 - Lower cost of sensor chip <u>and</u> fewer components in camera
 - Easy digital interface for faster camera design & time to market
 - Less image artifacts no blooming or smear, with same sensitivity
 - Higher dynamic range for security and auto applications
 - Digital output for faster readout speeds and frame rates
 - Direct addressing of pixels allows electronic pan/tilt/zoom
 - Faster design cycles means faster evolution path

CMOS APS OPERATION (1)



CMOS APS OPERATION (2)



CMOS APS OPERATION (3)



CMOS APS OPERATION (4)



CMOS APS OPERATION (5)



Pinned PD Photogate

- Better to replace poly MOSFET photogate with JFET photogate (a.k.a. pinned photodiode or buried photodiode)
- First demonstrated by JPL/Kodak collaboration in 1995



Lee, Gee, Guidash, Lee and Fossum 1995 IEEE CCD AIS Workshop

2D Potential Simulation



Color Filter Arrays and Microlenses

#1 .4um



Camera-on-a-chip

- Pixel array
- Signal chain
- ADC
- Digital logic
 - I/O interface
 - Timing and control
 - Exposure control
 - Color processing
- Ancillary circuits



2007 IISW
































• Sometimes it is a problem that not all pixels integrate for the same period of time -> moving object distortion

PICTURES FROM PC-TYPE CAMERA WITH ELECTRONIC ROLLING SHUTTER



CIF Resolution (352 x 288)



VGA Resolution (640 x 480)





Illustration of distortion

for moving objects





•Note that closer objects (objects passing faster in field of view) are more "tilted" compared to more distant objects.

•Not important for most tethered PC applications

First JPL CMOS APS Chip 4/93



JPL: Mendis & Fossum



- 28 x 28 element array
- 2 µm CMOS
- 40 μm x 40 μm pixels
- No on-chip timing or control

JPL Multiresolution Sensor



Process:	HP 1.2 um
	n-well CMOS
Pixel pitch:	24 um
No. pixels:	128 x 128
Pwr suppy:	5 volts
Saturation:	1200 mV
Conv. gain:	8 uV/e-
Noise:	116 uV rms
	15 e- rms
Dynamic	80 dB
Range:	
FPN:	<3 mV p-p
	<2.5 %
Power:	< 5 mW at 30Hz



Full resolution image 4x4 Averaged image (left) 1/4 Subsampled image (right)





Kemeny, Panicacci, Pain, Matthies, Fossum 1995 © 2008 E R Fossum

JPL/AT&T Digital CMOS APS



- 176x144 elements
- 20 μm pixel pitch
- Single-slope ADC per column
- 176 ADCs per chip
- 8 bit resolution
- 35 mW at 30 Hz
- 3.5 volt supply



Mendis, Inglis, Dickinson, and Fossum 1995

PB Prometheus







- 576 (H) x 432 (V)
- 20.9 μm PD pixel pitch
- 1.4 µm process
- 576 single slope ADCs
- digital & analog output ports

PB Very Low light sensor



low light image (~0.004 lux)



- 176 (H) x 144 (V) elements
- 30 µm E-PG pixel pitch
- 1.2 µm process
- 20 fps analog output

Xue 1996

PB 300 for Multimedia

- 640x487 (640x480 effective) pixels
- 320 column-parallel 8b ADCs
- 7.9 μm x 7.9 μm (1/3" optical format)
- Progressive scan, window readout
- 15,000+ gate on-chip logic
- >30 frames per sec (adj.)
- 5 V operation
- <300 mW total power
- Built-in autoexposure control
- On-chip biasing
- On-chip CFA
- >20 dB SNR @ 1 lux, 30 fps

Panicacci, Cho 1999





PBL080 Low Light Sensor

- 342 x 258 pixels
- 336 x 242 optical pixels
- 20 x 20 μm pixel pitch
- 64x on-chip gain
- On-chip gamma correction
- 8b digital output
- 10,000 gates on-chip logic
- EIA/NTSC timing
- 60 Hz progressive scan
- Autoexposure control
- --low light to sunlight @ F/1.4
- 150 mW

Barna, Ang, O'Conner, Wang 1999



200 lux room light, 60 Hz, F/1.4



1000x less light: 200 millilux, 60 Hz, F/1.4

Ultra High Dynamic (HiDy) Range Imaging System



PROCESSOR

ASIC

Dual Sensitivity Pixels (Linear Response)

High Sensitivity/High Gain 8-bit High Sensitivity/Low Gain 8-bit Low Sensitivity/High Gain 8-bit Low Sensitivity/Low Gain 8-bit

Fused Output 8-bit

- Linear outputs preserve contrast unlike logarithmic sensors
- Low susceptibility to FPN compared to logarithmic sensors
- Higher frame rate and less motion blur with © 2008 E R Fossum concurrent capturing







Wang 2000

Pill-Camera







- Pixel Format:
- Pixel Size:
- Frame Rate:
- ADC:
- Power Supply:
- Power:

256 X 256 10 µm X 10 µm 2 fps On-Chip, 8 bits 2.8 V 3 mW

© 2008 E R Fossum

Krymski

PB Dental Xray- Sensor



- Total chip size: 37 x 27 mm
- 900 (V) x 675 (H) elements
- 40 μm pixel pitch
- 2 µm CMOS process
- Differential analog output
- On-chip timing and control
- Event detector self-triggered readout
- World's largest CMOS chip in production © 2008 E R Fossum





visible flash

PB Buttable X-ray Sensor



- 466 x 466 elements
- 30 µm pixel pitch
- 0.8 µm process
- 2 column loss

Xue 1997



- 3-sides buttable
- P-channel PD-type pixel
- Differential analog output
- Some on-chip circuits

PB Optical Memory Readout





- 816 (V) x 616 (H) elements
- 17 μm PD pixel pitch
- 0.8 µm process
- special column-parallel comparator circuit

Panicacci 1997

PB1024 High Speed Sensor

- 1024x1024 elements
- 10 μm x 10 μm pixel pitch
- 0.5 μm CMOS
- 1024 on-chip 8b ADCs
- 8 digital output ports (64 pins)
- Open architecture
- Power: 95 mW @ 60 fps
- Power: 370 mW @ 574 fps
- By far, then world's pixel rate record of ALL image sensors (CCDs and CMOS)









Krymski, Van Blerkom, Bock, Anderson 1998

PBMV40 2352x1728 (4.1Mpix) 200fps ERS



- 4.1 Mpixel sensor
- 7 μm x 7 μm pixel pitch
- 16x10b digital output
- 200 fps ERS
- 960 Mbytes/sec at 66 MHz
- 4000 bits/lx-sec
- 3.3 volt operation



Krymski 2001

Shutter Efficiency



Ideal: Signal = Topen / Tperiod Signal₀

Actual: Signal = Topen / Tperiod Signal₀ + (1- ε) Signal₀ where ε is the shutter efficiency

CMOS SNAP

- Proprietary Photobit technology, 5-T pixel
- Normal photodiode
- Signal transferred to storage node in Nwell
- Storage node read out in usual way
- Diffusing photoelectrons do not affect storage
- Very high shutter efficiency >99.9%



PB MV13 1280x1024 (1.3Mpix) SNAP 1000 fps

- 1.3 Mpixel sensor
- 12 μ m x 12 μ m pixel pitch
- 0.35 μm CMOS
- High efficiency (>99.9%) freeze frame shutter
- Shutter speeds from 1/30th to 1/100,000th sec
- 10x10b digital output (100 pins)
- Open architecture
- 3.3 volt operation
- Power: <500 mW @500 fps
- 1000 bits/lx-s
- •©200018F094mnonochrome





1/605 sec=1652 usec Rolling shutter



1/33,000 sec = 30 usec Freeze frame shutter



Color image with rotating fan



High Speed Linear Sensor for Inspection



- 4096 x 1 linear array
- 7 um pixel pitch (28 mm long)
- Curtain-style readout
- 4 analog output ports, each 60 MHz
- 240 Mpix/sec total output rate
- 35,000 lines/sec
- 5 V operation
- Subwindowing allowed, from center

CMOS Image Sensors in 2008

- Basic operation still the same.
- Sharing of active transistor has improved fill factor
- ADC performance improved
- On-chip color processing improved
- Pixel pitch shrunk with smaller design rules

3.2 um 2T pixel 0.18 um process 8832 x 5748 = 52 Mpix @ 160 Mp/s



Figure 2 Readout equivalent circuit with pixel unit.



UDTV or Super Hi-Vision Sensor



- 7680 x 4320
- 33 Mpixels
- 60 fps
- 2 Gp/s

To The Near Future

 Main application of CMOS image sensors will be camera phones



Most of Market Controlled by 7 Players

Usual technology drivers will continue for next few years

- Smaller pixels (sub-diffraction limit or SDL)
 - Sensitivity
 - Full well
 - SNR
- Larger array sizes (up to 8-10 Mpixels)
 - Smaller pixels
 - Improved optics
- SoC will continue to demand premium
 - Despite trend to commoditize sensors thru 2-chip solutions.
 - Off-chip system integration too much work for camera phone OEMs.

Existing Solutions will be Tried and Tried Again

- Brute force shrink of pixel
 - Path of least resistance
- Stacked structures
 - Lag, noise and stability need to be overcome
- Backside illumination
 - Process flow development for high volume manufacturing
- Improved on-chip optics
 - Multi layer optics, optical funnels
- Improved dynamic range
 - Numerous adequate sensor solutions exist

Longer Term R&D Thoughts

- Stacked structures look interesting for capacitance improvement and optical improvement.
- Organic polymers for wavelength selectivity and lower dark current
- Jot/Digital Film paradigm shift
- Etc.

Gigapixel Digital Film Sensor (DFS)

State of the Art

- Pixel counts for consumers are in the 8-12 Mpixel range.
- Pixel counts for professional cameras are in the 20-40 Mpixel range
- Pixel counts for aerospace application are approaching 100 Mpixels.
- Pixel size is 2.2 um or smaller for common consumer applications.

Diffraction Limit

SDL Pixels are Coming

- Today you can make a 6T SRAM cell in less than 0.7 um² using 65 nm technology.
- CMOS active pixels are typically under 4T using shared readouts so 0.5 um pixel size (0.25 um²) seems around the corner.
- Never underestimate the force of marketing. Marketing > Engineering
- If you can't fix it, feature it. (purpose of this talk)

Consider 0.5 um pixel

About 40 0.5 um SDL pixels fit inside the Airy Disk
The Joy of SDL-Pixels (as seen by marketing)

For 0.5 um pixel:

- 3,456 x 2,304 (8 Mpixel)
- = 1.73 mm x 1.15 mm
- = 2 mm diagonal
- ~1/9 inch format
- 38,750 x 25,833 (1 Gpixel)
- = 19.5 mm x 13 mm
- = 23 mm diagonal
- APS-C is 22.5mm x 15 mm (30% larger)

Small engineering problems

- Reduced full-well capacity (Q = CV)
 - -0.5 um pixel has <1% of area of 5.6 um pixel
 - Reduced operating voltage
- Reduced SNR and DR
 - Fewer photoelectrons for same exposure
- Increased optical and carrier cross-talk
- Increased dark current due to higher doping and sharper corners
- Non-uniformity

SDL Pixels can oversample spatial dimensions



- No color aliasing
- Improved spatial resolution
- FPN reduction
- Will require more digital signal processing
 Doesn't really address full-
- well and SNR issues

Proposed Digital Film Sensor (DFS)

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Silver Halide Film







- AgX grains in emulsion exposed to light
- Grains hit by photon(s) are "tagged" = latent image
- Developer converts whole grain or washes it away

D-Log(H) Characteristic



Grain size – Speed trade off

- Larger grains have greater probability of being tagged for same exposure.
- Since entire grain becomes silver (black) upon exposure, larger grain size film seems more sensitive to light
- Trades spatial resolution for sensitivity

Translate from Film to Solid-State

- Specialized deep SDL pixel called "jot"
- Sensitive to single photoelectron
- If hit, jot is logic "1" upon or before readout
- Else, jot is logic "0"
- Could be a very-high-conversion-gain CMOS APS pixel
- Still sensitive to dark current
- Less sensitive to lag (stacked structure?)
- Eliminates full well and uniformity concerns

Digital Development in two steps

- First, area amplification (converting a whole grain to "1's")
- Second, converting binary data to gray tones.

1st Step of Digital Development



2nd Step of Digital Development



- Select kernel of certain area and weighting fnc.
- Convolve kernel with grain (or jot) pattern to measure density
- Gray-scale value proportional (or not) to density.
- Can resample convolution result at arbitrary resolution

Some interesting opportunities

- Can dynamically adjust grain size to trade spatial resolution for light sensitivity
- Can still do color using color filter arrays just treat each color plane independently
- Can scan out jot pattern multiple times per exposure since readout rates of binary image can be quite high (e.g. 50 nsec/row) making grains spatial and temporal
- Could apply neural nets to digital development

Some interesting questions

- What happens to photon shot noise in this DFS imaging paradigm. Same, or shaped?
- Will the D-logH characteristics of the DFS be more appealing to photography and cinematography?
- Does the DFS have scientific applications, esp. using the multi-scan mode (basically, a photoncounting sensor)?
- Can you use this in a cell-phone for video?
- What are dynamic range and SNR limitations for this device, and how does one optimally trade against spatial resolution (grain size)?

Conclusions

- CMOS image sensors are about as old as CCDs were in 1986
- Most improvements will be incremental
- Still accessible for start-ups thanks to foundry support
- Next generation image sensors will require some sort of paradigm shift <u>and</u> will need to be market driven.
- Jot-based sensors may be interesting